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Patent

Attorney's Docket No. 015290-426

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of)
)
William Frederick BOSCH) Group Art Unit: 1765
)
Application No.: 09/607,922) Examiner: L. T. Umez-Eronini
)
Filed: June 30, 2000) Confirmation No.: 9687
)
For: SEMICONDUCTOR PROCESSING)
EQUIPMENT HAVING IMPROVED)
PARTICLE PERFORMANCE)

AMENDMENT/REPLY TRANSMITTAL LETTER

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Enclosed is a reply for the above-identified patent application.

- ☐ A Petition for Extension of Time is also enclosed.
- ☐ A Terminal Disclaimer and a check for ☐ \$55.00 (2814) ☐ \$110.00 (1814) to cover the requisite Government fee are also enclosed.
- ☐ Also enclosed is _____.
- ☐ Small entity status is hereby claimed.
- ☐ Applicant(s) request continued examination under 37 C.F.R. § 1.114 and enclose the ☐ \$370.00 (2801) ☐ \$740.00 (1801) fee due under 37 C.F.R. § 1.17(e).
- ☐ Applicant(s) previously submitted ___, on ___, for which continued examination is requested.
- ☐ Applicant(s) request suspension of action by the Office until at least ___, which does not exceed three months from the filing of this RCE, in accordance with 37 C.F.R. § 1.103(c). The required fee under 37 C.F.R. § 1.17(i) is enclosed.
- ☐ A Request for Entry and Consideration of Submission under 37 C.F.R. § 1.129(a) (146/246) is also enclosed.
- ☐ No additional claim fee is required.



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AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the Official Action mailed August 13, 2002, please amend the above-identified application as follows.

IN THE CLAIMS:

Please replace Claim 14 and add new Claims 35 and 36 as follows:

14. (Amended) A method of processing semiconductor substrates and reducing particle contamination during processing of the substrates, the method comprising:
- (a) placing at least one substrate on a substrate holder in an interior space of a vacuum processing chamber, the processing chamber comprising a plasma reactor and including at least one ceramic part made of a non-oxide ceramic material and having a machined and/or sintered surface exposed to the interior space, the exposed surface having been treated to reduce particles of the non-oxide ceramic material attached to the exposed

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